All-2D Ambipolar ReSe₂ Field-Effect Transistors for Logic Circuit Applications

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Abstract

As various 2D materials have been synthesized, from semi-metal to insulator, the potential of 2D materials is extended wildly. Rhenium diselenide (ReSe₂), a kind of transition metal dichalcogenides (TMD), has a layer-number dependent bandgap ranging from 1.27 to 1.32 eV [1] for twolayers to ten-layers, is studied in this report. Due to the free of surface bonds and atomically flat surfaces, different 2D materials can form heterostructures without lattice mismatch by direct vertical stacking [2].

An optical microscope (OM) image of an all-2D ReSe₂ field-effect transistor (FET) is shown in Fig. 1a. The 2D channel material free of dangling bond surface is preserved by applying hBN as an insulator, which prevents surface roughness scattering. traditional metal Moreover, contacts replaced with graphene contact, which has excellent conductivity and tunable Fermi level characteristics, on 2D materials can avoid Fermi level pinning problem [3] and may improve device performance. **Figure 1b shows** the I_{ds} - V_{bg} for the ReSe₂ FET under various V_{ds} at different temperatures and shows clear ambipolar behaviour, which means the majority conduction carrier can be either electrons or holes and act as n-FET and p-FET. According to thermionic emission theory, the Schottky barrier height of the graphene contact can be derived from the curve fitting of Arrhenius plots and the derived results are shown in Fig. 1c. This tunability results in a much lower contact Schottky barrier height and clear ambipolarity in charge transport.

Inverters composed of the ReSe₂ FET and a resistor were fabricated to examine its circuit diagram and functions shown in **Fig. 2**a and 2b. The ReSe₂ FET operated in n-and p-FET conditions served as a put-down and -up device, respectively. Under the operation frequency of 10 Hz, it shows stable output levels and indicates a good potential for logic circuits with a single device.

References

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- [3] C. Gong, et al., Nano Lett., 14 (**2014**) 1714.



Figure 1: (a) OM image of a ReSe₂ FET. (b) Transfer characteristics at different temperatures of ReSe₂ FET. (c) Schottky barrier heights of graphene contact.



Figure 2: (a) The schematic and (b) V_{OUT}/V_{IN} versus time at the frequency = 10 Hz of the inverter circuit with the ReSe₂ FET operated in n- and p- FET conditions.